

IN THE CLAIMS

- 1 (Original). A method comprising:
forming a photoresist from a branched chain scission polymer.
- 2 (Original). The method of claim 1 including providing scissionable linkages and nonscissionable linkages in said polymer.
- 3 (Currently Amended). The method of claim 1 including providing a scissionable ~~scienable~~ linkage in a branch of said polymer.
- 4 (Original). The method of claim 1 including forming a photoresist including a polymer having a molecular weight greater than 10,000 Daltons.
- 5 (Original). The method of claim 1 including forming a photoresist including a polymer having a branch having a molecular weight greater than 5000 Daltons.
- 6 (Currently Amended). The method of claim 1 including forming a polymer including ~~oligo-4-hydroxystyrene~~ oligo-4-hydroxystyrene.
- 7 (Original). The method of claim 6 including forming tertiary carbonated linked branches.
- 8 (Original). The method of claim 6 including forming an oligo-1,4-dihydroxyphenylcarbonate-bis tertiary alcohol.
- 9 (Original). The method of claim 8 including appending a tertiary alcohol carbonate side chain on said polymer.